sulfidation resistance, and a sputtering target for forming a Ag alloy film which can form a Ag alloy film exhibiting stable in-plane properties even in the case where the film is formed on a substrate having a large area.

Means for Solving the Problem

[0009]

In order to solve the above problems, a Ag alloy film according to an aspect of the present invention has a composition including: In: 0.1% by mass to 1.5% by mass; and Cu: 1 ppm by mass to 50 ppm by mass, with the remainder being Ag and inevitable impurities.

[0010]

Since the Ag alloy film having these features according to the aspect of the present invention includes ~~2 ppm by mass to 20 ppm by mass~~1 ppm by mass to 50 ppm by mass of Cu, the occurrence of a Ag ion migration phenomenon can be suppressed and the migration resistance can be greatly improved.

In addition, since the Ag alloy film includes 0.1% by mass to 1.5% by mass of In, it is possible to improve the sulfidation resistance of the film. Accordingly, the deterioration of the properties can be suppressed during the production process and in the environment.

[0011]

Herein, it is preferable that the Ag alloy film according to the aspect of the present invention further includes Sb: 0.01% by mass to 1.0% by mass.

With regard to the above-mentioned display and LED, a heat treatment at a high temperature is carried out during the production process thereof. Therefore, the Ag alloy film used as the electrode and the wiring of the display and the LED is required to have